What Does The Future Hold?



NCAVS CMP Users Group April 12, 2006 Dean Freeman Research VP Gartner Dataquest



What Does the Future Hold

Economics

Moores Law

- Scaling
- Watts/performance
- Transistor
- Interconnect

Cycles

- Timing
- Materials



Semiconductor Capital Spending





A Big "New" Problem





Pat Gelsinger's Slide from ISSCC 2001

If nothing is done to reduce power, Moore's Law will be at risk

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http://www.intel.com/la

Labs

nte

Transistor Nanotechnology



Future options subject to change

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Source: Intel

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How far Does Silicon Really Go?

- Planar technology ~ 22-32 nm (12-16 nm Leff)
 FinFETs, Trigate
- Vertical Technology ~ 10-7 nm
 - Theoretical Si CMOS ~ 5 nm Gate length
- Nanotubes Introduced at 5-10 nm gate length
 - If manufacturing process is developed
- So how much further can Silicon go?
- And what"s next?



Limitations for CMOS

Transistor

- Power Vs. Current/Leakage
- Conventional Scaling is over
 - Architectural changes
 - Material changes
- Interconnect issues
 - Interconnect Delay
 - Resistance
 - Capacitance
- Manufacturing
 - Lithography
 - Uniformity

Transistor Technology 45 Nm





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Technology Challenges: New Transistor Architectures Ahoy



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Possible Applications of Carbon Nanotubes

 Transistors outperform silicon



Interconnects: vias & contact holes high current densities low resistance



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Nanotubes for Nanoscale Vias







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3-D IC



1. In aligned wafer bonding, wafers are aligned and bonded, then thinned and interconnected before additional stacking processes or dicing.





Thin Wafers and Die

(a) Rolled Wafer 10µm Thickness Wafer (b) Light Transparency



Spin Spin technology

Includes

- Quantum dots
- Single electron
- Primary Focus Memory applications
- Already in Manufacturing
 - MRAMS
 - Need to achieve higher density
- Can the technology become cost competitive with Flash and DRAM?
- This is the rule of thumb for any new technology!!



MRAM



Single Electron Transistors

- Was Heisenberg wrong?
 - Speed or location
 - Acts as wave or tunnels through barrier
- Interconnect
- Speed
- Ambient operation
- Unreliable computing
- Size of device??
- Still a long ways out

Quantum Dots

- Compound Semi materials
 - Uses Spin Spin technology
 - Electrons up, or down
 - 40 Qbits can account for 1 billion numbers
- Can be self aligned
- Quantum Computing
 - Alignment
 - Interconnect
 - Manufacturability
 - Size
 - Is it any smaller than Silicon
 - Ambient operation
 - Coherence
- A strong candidate but lots of work



Self Aligned Quantum Dots



GaAs Substrate with InAs Islands

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Molecular electronics

Organic/Molecular systems

- Good Storage Possible Memory applications
 - Zettacore/LSI logic
- Poor/slow switching speed. (Not good for Logic)
- Size
 - Many Molecular systems are larger than Silicon
- Can They be cost competitive?
 - How much does the molecule cost
- Will they survive the environment
 - lifetime



But will it work outside of the lab? or how to see through the hype

- Can it handle the Voltage and Current requirements?
- Can it match Silicon's packing density
- Can it shrink by 70 percent every 18 months to 2 years and cost less to manufacture?
- Does it meet the basic market requirements?
 - Gain, signal to noise etc.
- Can it be manufactured in a repeatable Manner?



Final Thoughts

- All devices do not scale equally
- Silicon will be the backbone for many years to come.
 - Competing technologies could use Si substrates
 - Silicon Quantum dots
- Silicon will exist with emerging technology
- CMOS will most likely extend into new technology.
- Unreliable computing most likely needed for single electron or cross bar technology.



- CMP will continue to be an enabler
- New materials will require new slurries/chemicals/pads
- CMP technology may be disruptive to current application

